

What is Claimed is:

1. A pattern collation apparatus for collating a
2 registration pattern with a collation pattern,
3 comprising:
4 first collation means for executing collation
5 between the registration pattern and the collation
6 pattern on the basis of a correlation value between the
7 patterns;
8 second collation means for executing collation
9 between the registration pattern and the collation
10 pattern on the basis of a feature parameter defined in
11 advance; and
12 collation determination means for determining
13 that the registration pattern coincides with the
14 collation pattern by using at least one of a collation
15 result by said first collation means and a collation
16 result by said second collation means.

2. An apparatus according to claim 1, wherein
2 when at least one of the collation result by said first
3 collation means and the collation result by said second
4 collation means indicates coincidence between the
5 registration pattern and the collation pattern, said
6 collation determination means determines that the
7 registration pattern coincides with the collation
8 pattern.

3. An apparatus according to claim 1, wherein
2 when the collation result by said first collation means
3 indicates coincidence between the registration pattern
4 and the collation pattern, said collation determination
5 means determines that the registration pattern coincides
6 with the collation pattern without executing collation
7 by said second collation means.

4. An apparatus according to claim 1, wherein
2 when the collation result by said second collation means
3 indicates coincidence between the registration pattern
4 and the collation pattern, said collation determination
5 means determines that the registration pattern coincides
6 with the collation pattern without executing collation
7 by said first collation means.

5. An apparatus according to claim 1, wherein
2 said apparatus further comprises execution order
3 designation means for allowing designation of an
4 execution order of collation by said first collation
5 means and collation by said second collation means, and
6 when a collation result by collation means
7 which is designated by said execution order designation
8 means to be executed first indicates coincidence between
9 the registration pattern and the collation pattern, said
10 collation determination means determines that the

11 registration pattern coincides with the collation
12 pattern without executing collation by collation means
13 which is designated to be executed later.

6. An apparatus according to claim 1, wherein
2 said apparatus further comprises
3 image inspection means for inspecting an image
4 of the collation pattern, and
5 execution order designation means for
6 designating an execution order of collation by said
7 first collation means and collation by said second
8 collation means on the basis of an inspection result of
9 the image of the collation pattern by said image
10 inspection means, and
11 when a collation result by collation means
12 which is designated by said execution order designation
13 means to be executed first indicates coincidence between
14 the registration pattern and the collation pattern, said
15 collation determination means determines that the
16 registration pattern coincides with the collation
17 pattern without executing collation by collation means
18 which is designated to be executed later.

7. A pattern collation apparatus comprising:
2 registration Fourier pattern data generation
3 means for executing N-dimensional discrete Fourier
4 transform for N-dimensional ($N \geq 1$) pattern data of a

5 registration pattern to generate registration Fourier
6 N-dimensional pattern data;
7 collation Fourier pattern data generation
8 means for executing N-dimensional discrete Fourier
9 transform for N-dimensional ($N \geq 1$) pattern data of a
10 collation pattern to generate collation Fourier
11 N-dimensional pattern data;
12 first amplitude suppression means for
13 executing amplitude suppression processing for the
14 registration Fourier N-dimensional pattern data;
15 second amplitude suppression means for
16 executing amplitude suppression processing for the
17 collation Fourier N-dimensional pattern data;
18 first polar coordinate system transformation
19 means for obtaining a polar coordinate system from a
20 coordinate system of the registration Fourier
21 N-dimensional pattern data that has undergone the
22 amplitude suppression processing by said first amplitude
23 suppression means;
24 second polar coordinate system transformation
25 means for obtaining a polar coordinate system from a
26 coordinate system of the collation Fourier N-dimensional
27 pattern data that has undergone the amplitude
28 suppression processing by said second amplitude
29 suppression means;
30 first collation means for collating, by an
31 amplitude suppression correlation method, the

32 registration Fourier N-dimensional pattern data of the
33 polar coordinate system obtained by said first polar
34 coordinate system transformation means with the
35 collation Fourier N-dimensional pattern data of the
36 polar coordinate system obtained by said second polar
37 coordinate system transformation means;
38 rotational shift amount measurement means for
39 obtaining a rotational shift amount between the pattern
40 data from a position of a correlation peak obtained in a
41 collation process by said first collation means;
42 rotational shift correction means for
43 executing rotational shift correction for one of the
44 registration pattern and the collation pattern on the
45 basis of the rotational shift amount obtained by said
46 rotational shift amount measurement means;
47 second collation means for, after rotational
48 shift correction by said rotational shift correction
49 means, collating the registration pattern with the
50 collation pattern by the amplitude suppression
51 correlation method;
52 vertical and horizontal shift amount
53 measurement means for obtaining vertical and horizontal
54 shift amounts between the pattern data from a position
55 of a correlation peak obtained in a collation process by
56 said second collation means;
57 rotational·vertical/horizontal shift
58 correction means for executing rotational shift and

59 vertical/horizontal shift correction for one of the
60 registration pattern and the collation pattern on the
61 basis of the rotational shift amount obtained by said
62 rotational shift amount measurement means and the
63 vertical and horizontal shift amounts obtained by said
64 vertical and horizontal shift amount measurement means;
65 third collation means for, after the
66 rotational shift and the vertical and horizontal shifts
67 are corrected by said rotational vertical/horizontal
68 shift correction means, collating the registration
69 pattern with the collation pattern on the basis of a
70 feature parameter defined in advance; and
71 collation determination means for determining
72 that the registration pattern coincides with the
73 collation pattern when at least one of collation results
74 by said first collation means, said second collation
75 means, and said third collation means indicates
76 coincidence between the registration pattern and the
77 collation pattern.

8. An apparatus according to claim 7, wherein
2 said first polar coordinate system
3 transformation means transforms the coordinate system of
4 the registration Fourier N-dimensional pattern data that
5 has undergone the amplitude suppression processing by
6 said first amplitude suppression means into the polar
7 coordinate system, and

8 said second polar coordinate system
9 transformation means transforms the coordinate system of
10 the collation Fourier N-dimensional pattern data that
11 has undergone the amplitude suppression processing by
12 said second amplitude suppression means into the polar
13 coordinate system.

9. An apparatus according to claim 7, wherein
2 said first polar coordinate system
3 transformation means adds a sign of a phase to the
4 registration Fourier N-dimensional pattern data that has
5 undergone the amplitude suppression processing by said
6 first amplitude suppression means, extracts only an
7 amplitude component with the sign, and then transforms
8 the coordinate system of the registration Fourier
9 N-dimensional pattern data into the polar coordinate
10 system, and
11 said second polar coordinate system
12 transformation means adds a sign of a phase to the
13 collation Fourier N-dimensional pattern data that has
14 undergone the amplitude suppression processing by said
15 second amplitude suppression means, extracts only an
16 amplitude component with the sign, and then transforms
17 the coordinate system of the collation Fourier
18 N-dimensional pattern data into the polar coordinate
19 system.

10. An apparatus according to claim 7, wherein
2 said first amplitude suppression means removes
3 a phase component of the registration Fourier
4 N-dimensional pattern data and then executes the
5 amplitude suppression processing for the registration
6 Fourier N-dimensional pattern data, and
7 said second amplitude suppression means
8 removes a phase component of the collation Fourier
9 N-dimensional pattern data and then executes the
10 amplitude suppression processing for the collation
11 Fourier N-dimensional pattern data.